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NEWS	1		Web Page for STN Seminar Schedule - N. America
NEWS	2	JUL 28	CA/Caplus patent coverage enhanced
NEWS	3	JUL 28	EFFULL enhanced with additional legal status information from the epline Register
NEWS	4	JUL 28	IFICDB, IFIPAT, and IFIUDB reloaded with enhancements
NEWS	5	JUL 28	STN Viewer performance improved
NEWS	6	AUG 01	INPADOCDB and INPAFAMDB coverage enhanced
NEWS	7	AUG 13	CA/Caplus enhanced with printed Chemical Abstracts page images from 1967-1998
NEWS	8	AUG 15	CAOLD to be discontinued on December 31, 2008
NEWS	9	AUG 15	CAplus currency for Korean patents enhanced
NEWS	10	AUG 27	CAS definition of basic patents expanded to ensure comprehensive access to substance and sequence information
NEWS	11	SEP 18	Support for STN Express, Versions 6.01 and earlier, to be discontinued
NEWS	12	SEP 25	CA/Caplus current-awareness alert options enhanced to accommodate supplemental CAS indexing of exemplified prophetic substances
NEWS	13	SEP 26	WPIDS, WPINDEX, and WPIX coverage of Chinese and and Korean patents enhanced
NEWS	14	SEP 29	IFICLS enhanced with new super search field
NEWS	15	SEP 29	EMBASE and EMBAL enhanced with new search and display fields
NEWS	16	SEP 30	CAS patent coverage enhanced to include exemplified prophetic substances identified in new Japanese-language patents
NEWS	17	OCT 07	EFFULL enhanced with full implementation of EPC2000
NEWS	18	OCT 07	Multiple databases enhanced for more flexible patent number searching
NEWS	19	OCT 22	Current-awareness alert (SDI) setup and editing enhanced
NEWS	20	OCT 22	WPIDS, WPINDEX, and WPIX enhanced with Canadian PCT Applications
NEWS	21	OCT 24	CHEMLIST enhanced with intermediate list of pre-registered REACH substances
NEWS	22	NOV 21	CAS patent coverage to include exemplified prophetic substances identified in English-, French-, German-, and Japanese-language basic patents from 2004-present
NEWS	23	NOV 26	MARPAT enhanced with FSORT command
NEWS	24	NOV 26	MEDLINE year-end processing temporarily halts availability of new fully-indexed citations
NEWS	25	NOV 26	CHEMSAFE now available on STN Easy
NEWS	26	NOV 26	Two new SET commands increase convenience of STN searching
NEWS	27	DEC 01	ChemPort single article sales feature unavailable

NEWS EXPRESS JUNE 27 08 CURRENT WINDOWS VERSION IS V8.3,
AND CURRENT DISCOVER FILE IS DATED 23 JUNE 2008.

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* * * * * STN Columbus * * * * *

FILE 'HOME' ENTERED AT 09:45:53 ON 01 DEC 2008

=> file reg		
COST IN U.S. DOLLARS	SINCE FILE	TOTAL
	ENTRY	SESSION
FULL ESTIMATED COST	0.21	0.21

FILE 'REGISTRY' ENTERED AT 09:46:10 ON 01 DEC 2008
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STRUCTURE FILE UPDATES: 28 NOV 2008 HIGHEST RN 1076692-21-1
DICTIONARY FILE UPDATES: 28 NOV 2008 HIGHEST RN 1076692-21-1

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TSCA INFORMATION NOW CURRENT THROUGH July 5, 2008.

Please note that search-term pricing does apply when conducting SmartSELECT searches.

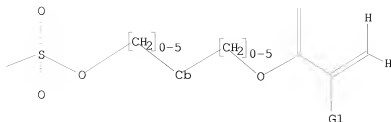
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L1 STRUCTURE UPLOADED

=> d l1
L1 HAS NO ANSWERS
L1 STR



G1 H, Me, Et, CF3, CCl3, CBr3, Cl3

G2 X, Ak, O

Structure attributes must be viewed using STN Express query preparation.

=> s l1

SAMPLE SEARCH INITIATED 09:46:39 FILE 'REGISTRY'

SAMPLE SCREEN SEARCH COMPLETED - 1468 TO ITERATE

100.0% PROCESSED 1468 ITERATIONS

0 ANSWERS

SEARCH TIME: 00.00.01

FULL FILE PROJECTIONS: ONLINE **COMPLETE**

BATCH **COMPLETE**

PROJECTED ITERATIONS: 27062 TO 31658

PROJECTED ANSWERS: 0 TO 0

L2 0 SEA SSS SAM L1

=> s l1 full

FULL SEARCH INITIATED 09:46:44 FILE 'REGISTRY'

FULL SCREEN SEARCH COMPLETED - 29287 TO ITERATE

100.0% PROCESSED 29287 ITERATIONS

2 ANSWERS

SEARCH TIME: 00.00.01

L3 2 SEA SSS FUL L1

=> file caplus

COST IN U.S. DOLLARS

SINCE FILE

TOTAL

ENTRY

SESSION

FULL ESTIMATED COST

178.36

178.57

FILE 'CAPLUS' ENTERED AT 09:46:49 ON 01 DEC 2008

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FILE COVERS 1907 - 1 Dec 2008 VOL 149 ISS 23

FILE LAST UPDATED: 30 Nov 2008 (20081130/ED)

Caplus now includes complete International Patent Classification (IPC) reclassification data for the third quarter of 2008.

Effective October 17, 2005, revised CAS Information Use Policies apply. They are available for your review at:

<http://www.cas.org/legal/infopolicy.html>

=> s l3

L4 7 L3

=> d l4 ibib abs hitstr l-

YOU HAVE REQUESTED DATA FROM 7 ANSWERS - CONTINUE? Y/(N):y

L4 ANSWER 1 OF 7 CAPLUS COPYRIGHT 2008 ACS on STN

ACCESSION NUMBER: 2008:1247016 CAPLUS

DOCUMENT NUMBER: 149:471962

TITLE: Adamantane derivative, resin composition using the same, and resin cured product

INVENTOR(S): Ito, Katsuki; Okada, Yasunari; Yamane, Hideki; Yamao, Shinobu

PATENT ASSIGNEE(S): Idemitsu Kosan Co., Ltd., Japan

SOURCE: PCT Int. Appl., 47pp.

CODEN: PIXXD2

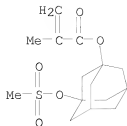
DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

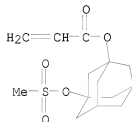
PATENT INFORMATION:

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WO 2008123490	A1	20081016	WO 2008-JP56303	20080331
W:	AE, AG, AL, AM, AO, AT, AU, AZ, BA, BB, BG, BH, BR, BW, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DO, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, GT, HN, HR, HU, ID, IL, IN, IS, KE, KG, KM, KN, KP, KR, KZ, LA, LC, LK, LR, LS, LT, LU, LY, MA, MD, ME, MG, MK, MN, MW, MX, MY, MZ, NA, NG, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RS, RU, SC, SD, SE, SG, SK, SL, SM, SV, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, ZA, ZM, ZW			
RW:	AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HR, HU, IE, IS, IT, LT, LU, LV, MC, MT, NL, NO, PL, PT, RO, SE, SI, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG, BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM			
JP 2008255188	A	20081023	JP 2007-97485	20070403
PRIORITY APPLN. INFO.:			JP 2007-97485	A 20070403
AB	Disclosed is a cured product of an adamantane derivative having a specific structure, which is excellent in transparency, optical characteristics such as (long-term) light resistance, long-term heat resistance, dielectric constant and mech. properties. This resin cured product is suitably used in the fields of electronic/optical material.			
IT	861675-46-9, 3-(Methanesulfonyloxy)-1-adamantyl methacrylate 928833-08-3 RL: RCT (Reactant); RACT (Reactant or reagent) (adamantane derivative, resin composition using the same, and resin cured product)			
RN	861675-46-9 CAPLUS			
CN	2-Propenoic acid, 2-methyl-, 3- [(methylsulfonyl)oxy]tricyclo[3.3.1.1 ^{3,7}]dec-1-yl ester (CA INDEX NAME)			



RN 928833-08-3 CAPLUS

CN 2-Propenoic acid, 3-[(methylsulfonyl)oxy]tricyclo[3.3.1.1.3,7]dec-1-yl ester (CA INDEX NAME)



REFERENCE COUNT: 7 THERE ARE 7 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L4 ANSWER 2 OF 7 CAPLUS COPYRIGHT 2008 ACS on STN

ACCESSION NUMBER: 2008:156855 CAPLUS

DOCUMENT NUMBER: 148:239643

TITLE: Polymerizable compound having adamantane structures for photoresist compositions

INVENTOR(S): Hatakeyama, Naoyoshi; Ono, Hidetoshi; Ito, Katsuki

PATENT ASSIGNEE(S): Idemitsu Kosan Co., Ltd., Japan

SOURCE: PCT Int. Appl., 97pp.

CODEN: PIXXD2

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

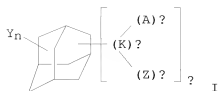
PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
WO 2008015876	A1	20080207	WO 2007-JP63641	20070709
W:	AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BH, BR, BW, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DO, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, GT, HN, HR, HU, ID, IL, IN, IS, JP, KE, KG, KM, KN, KP, KR, KZ, LA, LC, LK, LR, LS, LT, LU, LY, MA, MD, ME, MG, MK, MN, MW, MX, MY, MZ, NA, NG, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RS, RU, SC, SD, SE, SG, SK, SL, SM, SV, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, ZA, ZM, ZW			
RW:	AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IS, IT, LT, LU, LV, MC, MT, NL, PL, PT, RO, SE, SI, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG, BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM			

PRIORITY APPLN. INFO.:

JP 2006-213364

A 20060804

GI

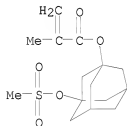


AB The present invention relates to fluorinated adamantane-containing polymerizable compds. I, wherein A = CH₂:CR₀ or CH.tplbond.C; R₀ = H, F, Me, Et, or trifluoromethyl; K = connecting group; Z = fluoro-containing substituent; Y = H, C1-10 alkyl, halogen, OH, SH, methylamino, :O, or :S; α = ≥1 integer; β, γ = ≥0 integer; δ = 1-16 integer; and n = 0-15 integer (δ + n = 16). In the filed of photolithog., by using the polymerizable compds. having an adamantane structure and the resin composition, it becomes possible to reduce the permeability of a liquid immersion medium and improve the dry-etching resistance in a liquid immersion exposure method and to reduce the adhesion to a mold and improve the dry-etching resistance in a nanoimprint method. Thus, 40.20 mmol 3-methanesulfonyloxy-1-adamantyl methacrylate and 40 mmol undecafluorocyclohexylmethanol were reacted at 120° for 6 h to give 3-[(undecafluorohexyl)methoxy]-1-adamantyl methacrylate with yield 61.3%.

IT 861675-46-9
 RL: RCT (Reactant); RACT (Reactant or reagent)
 (preparation of polymerizable compound having adamantane structures for photoresist compns.)

RN 861675-46-9 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 3-[(methylsulfonyl)oxy]tricyclo[3.3.1.1^{3,7}]dec-1-yl ester (CA INDEX NAME)



REFERENCE COUNT: 7 THERE ARE 7 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L4 ANSWER 3 OF 7 CAPLUS COPYRIGHT 2008 ACS on SIN

ACCESSION NUMBER: 2007:283958 CAPLUS

DOCUMENT NUMBER: 146:338316

TITLE: Adamantane derivatives useful for photolithog. and photoresists

INVENTOR(S): Ono, Hidetoshi; Hatakeyama, Naoyoshi; Okada, Yasunari; Ito, Katsuki

PATENT ASSIGNEE(S): Idemitsu Kosan Co., Ltd., Japan

SOURCE: PCI Int. Appl., 40pp.
 CODEN: PIXXD2

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

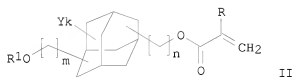
FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
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WO 2007029442 A1 20070315 WO 2006-JP315642 20060808
W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, HN, HR, HU, ID, IL, IN, IS, KE, KG, KM, KN, KP, KR, KZ, LA, LC, LK, LR, LS, LT, LU, LV, LY, MA, MD, MG, MK, MN, MW, MX, MZ, NA, NG, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RS, RU, SC, SD, SE, SG, SK, SL, SM, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, ZA, ZM, ZW
RW: AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IS, IT, LT, LU, LV, MC, NL, PL, PT, RO, SE, SI, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG, BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM

JP 2007077024 A 20070329 JP 2005-262633 20050909
PRIORITY APPLN. INFO.: JP 2005-262633 A 20050909
OTHER SOURCE(S): MARPAT 146:338316
GI

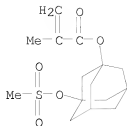


AB The present invention relates to adamantane derivs. I or II, wherein R = H, Me, or trifluoromethyl; Y = C1-10 alkyl, halogeno, or hydroxy (two Y's may be :O); R1 = C2-20 hydrocarbon group containing ≥ 1 hydroxy group; k = 0-14 integer; and m, n = 0 or 1. Thus, 1.0 mol Adamantate HM and 1.2 mol methanesulfonyl chloride were reacted, the resulting 3-methanesulfonyloxy-1-adamantyl acrylate was reacted with ethylene glycol in the presence of p-methoxyphenol to give 3-(2-hydroxyethoxy)-1-adamantyl methacrylate, 2.61 g of which was polymerized with 12.68 g 5-[3,3,3-trifluoro-2-hydroxy-2-(trifluoromethyl)propyl]bicyclo[2.2.1]hept-2-yl methacrylate to give a copolymer with Mw 7000 and polydispersity 1.57.

IT 861675-46-9P 928833-08-3P
RL: IMF (Industrial manufacture); RCT (Reactant); PREP (Preparation); RACT (Reactant or reagent)
(intermediate; preparation of adamantane derivs. useful for photolithog. and photoresists)

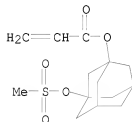
RN 861675-46-9 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 3-
[(methylsulfonyloxy)tricyclo[3.3.1.1^{3,7}]dec-1-yl ester (CA INDEX NAME)



RN 928833-08-3 CAPLUS

CN 2-Propenoic acid, 3-[(methylsulfonyl)oxy]tricyclo[3.3.1.1.3]dec-1-yl ester (CA INDEX NAME)



REFERENCE COUNT: 8 THERE ARE 8 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L4 ANSWER 4 OF 7 CAPLUS COPYRIGHT 2008 ACS on STN

ACCESSION NUMBER: 2007:281886 CAPLUS

DOCUMENT NUMBER: 146:339083

TITLE: Polymers for negative resist compositions with good resolution

INVENTOR(S): Iwashita, Jun; Kusaka, Ayako

PATENT ASSIGNEE(S): Tokyo Ohka Kogyo Co., Ltd., Japan

SOURCE: PCT Int. Appl., 69pp.

CODEN: PIXXD2

DOCUMENT TYPE: Patent

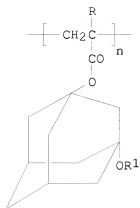
LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

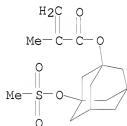
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
WO 2007029462	A1	20070315	WO 2006-JP316160	20060817
W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, HN, HR, HU, ID, IL, IN, IS, KE, KG, KM, KN, KP, KR, KZ, LA, LC, LK, LR, LS, LT, LU, LV, LY, MA, MD, MG, MK, MN, MW, MX, MY, MZ, NA, NG, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RS, RU, SC, SD, SE, SG, SK, SL, SM, SV, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, ZA, ZM, ZW RW: AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IS, IT, LT, LU, LV, MC, NL, PL, PT, RO, SE, SI, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG, BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM JP 2007070562 A 20070322 JP 2005-261848 20050909 PRIORITY APPLN. INFO.: JP 2005-261848 A 20050909				

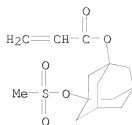
GI



- AB The title neg. resist comps. comprise (A) an alkali-soluble resin containing structural unit I, (B) an acid generator generating an acid upon exposure to light, and (C) a crosslinking agent, wherein R = H, halogeno, alkyl, or haloalkyl and R1 = hydroxylated alkyl. Thus, 1.0 mol Adamantate HA (3-hydroxy-1-adamantyl acrylate) and 1.2 mol methanesulfonyl chloride were reacted in the presence of triethylamine, and reacted with ethylene glycol to give 3-(2-hydroxyethyl)-1-adamantyl acrylate, 2.48 g of which was polymerized with 12.68 g 5-[3,3,3-trifluoro-2-hydroxy-2-(trifluoromethyl)propyl]bicyclo[2.2.1]hept-2-yl acrylate to give a copolymer with Mw 4000 and polydispersity 1.44.
- IT 861675-46-9P, 3-Methanesulfonyloxy-1-adamantyl methacrylate
928833-08-3P
RL: IMF (Industrial manufacture); RCT (Reactant); PREP (Preparation); RACT (Reactant or reagent)
(intermediate in monomer preparation; polymers for neg. resist comps. with good resolution)
- RN 861675-46-9 CAPLUS
- CN 2-Propenoic acid, 2-methyl-, 3-
[(methylsulfonyl)oxy]tricyclo[3.3.1.1.3]dec-1-yl ester (CA INDEX NAME)



- RN 928833-08-3 CAPLUS
- CN 2-Propenoic acid, 3-[(methylsulfonyl)oxy]tricyclo[3.3.1.1.3]dec-1-yl
ester (CA INDEX NAME)



REFERENCE COUNT: 10 THERE ARE 10 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L4 ANSWER 5 OF 7 CAPLUS COPYRIGHT 2008 ACS on SIN

ACCESSION NUMBER: 2006:1225162 CAPLUS

DOCUMENT NUMBER: 146:16291

TITLE: Polymerizable compound for photoresist, polymer thereof, and photoresist composition containing such polymer

INVENTOR(S): Hatakeyama, Naoyoshi; Ito, Katsuki; Ono, Hidetoshi; Matsumoto, Nobuaki

PATENT ASSIGNEE(S): Idemitsu Kosan Co., Ltd., Japan

SOURCE: PCT Int. Appl., 76pp.

CODEN: PIXXD2

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
WO 2006123605	A1	20061123	WO 2006-JP309646	20060515
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RW:	AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IS, IT, LT, LU, LV, MC, NL, PL, PT, RO, SE, SI, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG, BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM			
EP 1882705	A1	20080130	EP 2006-746393	20060515
R:	BE, DE, FR, GB			
KR 2008008320	A	20080123	KR 2007-722501	20071002
CN 101180324	A	20080514	CN 2006-80017257	20071119
PRIORITY APPLN. INFO.:			JP 2005-148737	A 20050520
			WO 2006-JP309646	W 20060515

OTHER SOURCE(S): MARPAT 146:16291

AB Disclosed is a polymerizable compound having an alicyclic structure represented by the general formula

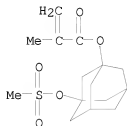
$$L-[(K)\alpha(-A)\beta(Z)\gamma]\delta$$
 or $[Z-(K2)b-d-L-[(K1)a-A]c(A$
 = vinyl, acetyl, norbornenyl; K, K1-2= carbonyl, thiocarbonyl, ketimine, etc.; Z = alkyl, hydrogen, hydroxy, etc.; $\alpha-\gamma$ = integer ≥ 1 ; δ = integer 1-16;) and a polymerizable group. The polymerizable compound exhibits high adhesion to substrates and reduced swelling during development, while having high dry-etching resistance. In addition, this polymerizable compound takes in only a small amount of water when it is exposed to light in water. Also disclosed are a polymer of such a

polymerizable compound, a method for producing such a polymerizable compound, and a photoresist composition containing such a polymer.

IT 861675-46-9, 3-(Methanesulfonyloxy)-1-adamantyl methacrylate
 RL: RCT (Reactant); RACT (Reactant or reagent)
 (polymerizable compound for photoresist)

RN 861675-46-9 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 3-
 [(methylsulfonyl)oxy]tricyclo[3.3.1.1^{3,7}]dec-1-yl ester (CA INDEX NAME)



REFERENCE COUNT: 9 THERE ARE 9 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L4 ANSWER 6 OF 7 CAPLUS COPYRIGHT 2008 ACS on SIN

ACCESSION NUMBER: 2005:822398 CAPLUS

DOCUMENT NUMBER: 143:212288

TITLE: Methanesulfonyloxy-substituted adamantyl
 (meth)acrylates as materials for photolithography and their manufacture

INVENTOR(S): Hatakeyama, Naoyoshi; Tanaka, Shinji; Ono, Hidetoshi

PATENT ASSIGNEE(S): Idemitsu Kosan Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 9 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

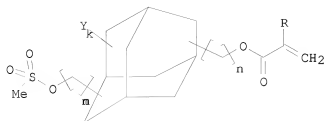
FAMILY ACC. NUM. COUNT: 2

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2005220066	A	20050818	JP 2004-29034	20040205
WO 2005075406	A1	20050818	WO 2005-JP1404	20050201
W:	AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NA, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW			
RW:	BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM, AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IS, IT, LT, LU, MC, NL, PL, PT, RO, SE, SI, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG			
EP 1712542	A1	20061018	EP 2005-709550	20050201
R:	BE, DE, FR, GB			
CN 1914147	A	20070214	CN 2005-80003712	20050201
US 20070129532	A1	20070607	US 2007-588080	20070110
PRIORITY APPLN. INFO.:			JP 2004-29034	A 20040205
			JP 2004-66626	A 20040310
			JP 2004-218686	A 20040727
			JP 2004-296542	A 20041008
			WO 2005-JP1404	W 20050201

OTHER SOURCE(S):
GI

MARPAT 143:212288



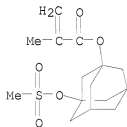
II

AB Title compds. I (R = H, Me, CF₃; Y = C1-10 alkyl, halo, OH; 2 Y may be linked to form :O; k = 0-14; m, n = 0-4) are manufactured by reaction of the corresponding alcs. with MeSO₂X (X = halo). Thus, 118.16 g Adamantate HM (3-hydroxy-1-adamantyl methacrylate) was mesylated in the presence of Et₃N in THF, treated with water, concentrated, extracted with ether, the extract treated with MeOH to remove polymers, and worked-up to give 102.21 g 3-methanesulfonyloxy-1-adamantyl methacrylate with 98.9% purity.

IT 861675-46-9P
RL: IMF (Industrial manufacture); PUR (Purification or recovery); PREP (Preparation)
(manufacture of methanesulfonyloxy-substituted adamantyl (meth)acrylates as materials for photolithog.)

RN 861675-46-9 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 3-[(methylsulfonyl)oxy]tricyclo[3.3.1.1^{3,7}]dec-1-yl ester (CA INDEX NAME)



L4 ANSWER 7 OF 7 CAPLUS COPYRIGHT 2008 ACS on STN

ACCESSION NUMBER: 2005:811728 CAPLUS

DOCUMENT NUMBER: 143:230354

TITLE: Preparation of adamantane derivatives

INVENTOR(S): Hatakeyama, Naoyoshi; Tanaka, Shinji; Ono, Hidetoshi; Okada, Yasunari

PATENT ASSIGNEE(S): Idemitsu Kosan Co., Ltd., Japan

SOURCE: PCT Int. Appl., 37 pp.
CODEN: PIXXD2

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 2

PATENT INFORMATION:

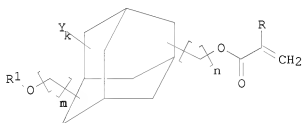
PATENT NO.

KIND DATE

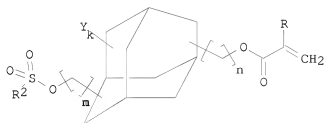
APPLICATION NO.

DATE

WO 2005075406	A1	20050818	WO 2005-JP1404	20050201
W:	AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NA, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW			
RW:	BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM, AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IS, IT, LT, LU, MC, NL, PL, PT, RO, SE, SI, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG			
JP 2005220066	A	20050818	JP 2004-29034	20040205
JP 2006104173	A	20060420	JP 2004-296542	20041008
EP 1712542	A1	20061018	EP 2005-709550	20050201
R:	BE, DE, FR, GB			
CN 1914147	A	20070214	CN 2005-80003712	20050201
JP 2006063061	A	20060309	JP 2005-67044	20050310
US 20070129532	A1	20070607	US 2007-588080	20070110
PRIORITY APPLN. INFO.:			JP 2004-29034	A 20040205
			JP 2004-66626	A 20040310
			JP 2004-218686	A 20040727
			JP 2004-296542	A 20041008
			WO 2005-JP1404	W 20050201
OTHER SOURCE(S):	MARPAT 143:230354			
GI				



I



II

AB The present invention relates to an adamantane derivative having a structure I and II useful as a monomer for functional resins such as a photosensitive resin in the field of photolithog., wherein R = H, CH₃, or CF₃; R₁ = C₁-10 alkyl or cycloalkyl; R₂ = C₁-10 alkyl, Ph, alkylphenyl, or CF₃; Y = C₁-10 alkyl, halogen, OH, or ketone formed by multiple Y; k = 0-14 integer; and m, n = 0-4 integer. An alc. form of an adamantane compound is reacted with a sulfonyl compound to obtain the adamantane derivative II, which is then reacted with an alc. to obtain the adamantane derivative I. Thus, 500 mmol Adamantane HM (3-hydroxy-1-adamantyl methacrylate) and 600 mmol methanesulfonyl chloride were stirred to give 156.26 g

3-methanesulfonyloxy-1-adamantyl methacrylate, which was reacted with 6849 mmol 2-methyl-2-butanol in the presence of DBU and methoxyquinone at 120° for 36 h to give 81.0 g 3-tert-pentyloxy-1-adamantyl methacrylate with purity 99.8%.

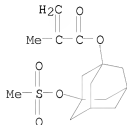
IT 861675-46-9P

RL: IMF (Industrial manufacture); RGT (Reagent); PREP (Preparation); RACT (Reactant or reagent)

(intermediate; preparation of adamantane derivs.)

RN 861675-46-9 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 3-[(methylsulfonyl)oxy]tricyclo[3.3.1.1^{3,7}]dec-1-yl ester (CA INDEX NAME)



REFERENCE COUNT:

6

THERE ARE 6 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

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